

**AMENDMENTS TO THE DRAWINGS**

**IN THE DRAWINGS**

“Replacement Sheet” is attached which includes a clean version of amended Figures 1 through 5. The attached sheet replaces the original sheet including Figures 1-5.

“Annotated Sheets Showing Change” is also attached which includes a marked-up version of Figures 1-5.

The Office Action noted that Figures 1-5 should be designated by a legend such as -- Prior Art --. This has been done. Review and approval of the proposed drawing correction is respectfully requested.

**REMARKS**

In response to the Office Action mailed July 26, 2005, Applicants respectfully request reconsideration.

The Office Action acknowledges Applicants' claim for foreign priority based on application No. IT MI99A 001768, filed August 5, 1999 in Italy. However, the Office Action indicates that it appears that Applicants have not filed a certified copy of the priority application. Applicants wish to confirm their claim for Paris Convention priority and note that the required certified copy of the priority application was filed in parent application Serial No. 09/632,031, of which the present application is a division. Therefore, Applicants believe that all requirements to make and perfect their Paris Convention claim have been met and respectfully request acknowledgement of the same in the next Office Action.

The Office Action indicates that Figs. 1-5 should be designated by a legend such as --Prior Art--. The drawings have been so corrected. Review and approval of the corrected drawings is respectfully requested.

The disclosure was objected to because of a number of informalities noted on page 3 of the Office Action. All of these informalities have been corrected and withdrawal of this objection is respectfully requested.

Claims-7 were rejected under 35 USC §112, first paragraph as failing to comply with the enablement requirement. In particular, it appears that the Office Action objects to the use of the word "electromagnetic" simply because that word is not found literally in the application. To overcome this rejection, Applicants have changed the word "electromagnetic" to --incident-- so that the language in the claims now tracks the language in the specification. However, Applicants wish to note, as set forth in the application, that the incident wave can be a luminous wave, a lamp, or a laser. All of these waves are forms of electromagnetic radiation and therefore Applicants believe that the language "incident wave" as set forth in the claims covers all of these different forms of light energy. Accordingly, in view of the amendment to claim 7, Applicants respectfully request that the rejection under 35 USC §112, first paragraph, of claims 7-9 be withdrawn.

The Office Action rejected claims 7-9 under 35 USC §102(b) as being anticipated by Brock et al. et al. With respect to claim 7, the Office Action asserts that Brock et al. discloses a method of

defining contacts on an IC device using electromagnetic wave. According to the Office Action, the method includes the steps of providing an IC device substrate 15a ((fig. 1A), a first plate (mask) 10e, 10f (fig. 5A) of material transparent (col. 1, line 58) and a layer of phase shifting material 12e, 16f, 46 (fig. 6B; fig. 4B) having an etch window 40 (fig. 4A; col. 2, line 46; col. 4, lines 33-34; col. 5, lines 14-19) defining at least six sides (fig. 4A); and directing the electromagnetic wave (col. 1, lines 25-29) at the substrate through the layer of phase shift 12e, 16f material and the first plate 10e, 10f. Applicants respectfully traverse this rejection.

Brock et al. is directed to a phase-shifting transparent lithographic mask for creating contiguous structures from non-contiguous mask areas. Brock et al. contains no teaching or suggestion or recognition of the problem of side lobes as discussed in the present invention.

By contrast, claim 7 recites a method of defining contacts on an integrated circuit device using an incident wave including: providing an integrated circuit device substrate, a first plate of material transparent to the incident wave placed over the substrate, and a layer of phase shift material having defined therethrough a regular polygon-shaped etch window with at least six sides; and directing the incident wave at the substrate through the layer of phase shift material and first plate. Nowhere does Brock et al. teach or suggest “a layer of phase shift material having defined therethrough a regular polygon-shaped etch window with at least six sides”. None of the etch windows in Brock et al. appear to be regular polygons as claimed in claim 7. Accordingly, claim 7 distinguishes over Brock et al. and is in allowable condition.

Claims 8-9 depend from claim 7 and are allowable for at least the same reasons.

Accordingly, Applicants respectfully request that the rejection under 35 USC §102(b) be withdrawn.

In view of the foregoing amendments and remarks, this application should now be in condition for allowance. A notice to this effect is respectfully requested. If the Examiner believes, after this amendment, that the application is not in condition for allowance, the Examiner is requested to call the undersigned at the telephone number listed below.

If this response is not considered timely filed and if a request for an extension of time is otherwise absent, Applicant hereby requests any necessary extension of time. If there is a fee occasioned by this response, including an extension fee, that is not covered by an enclosed check,

Application No. 10/693479  
Amendment dated January 26, 2006  
Reply to Office Action of July 26, 2005

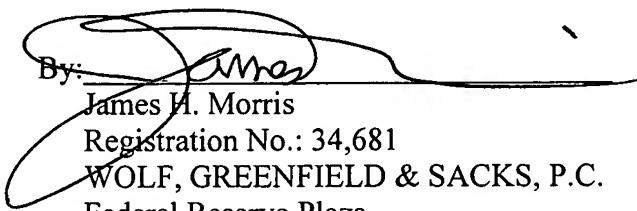
9

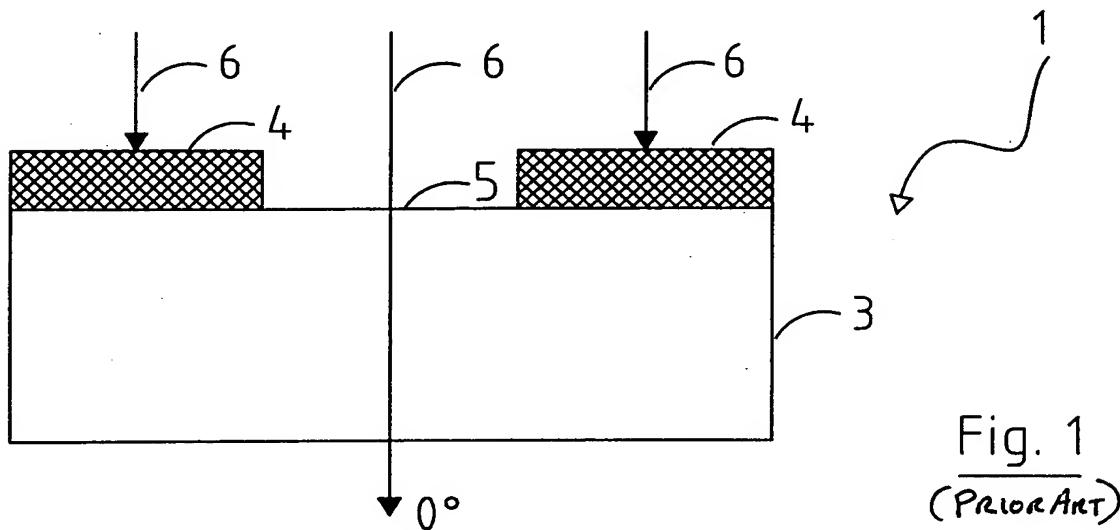
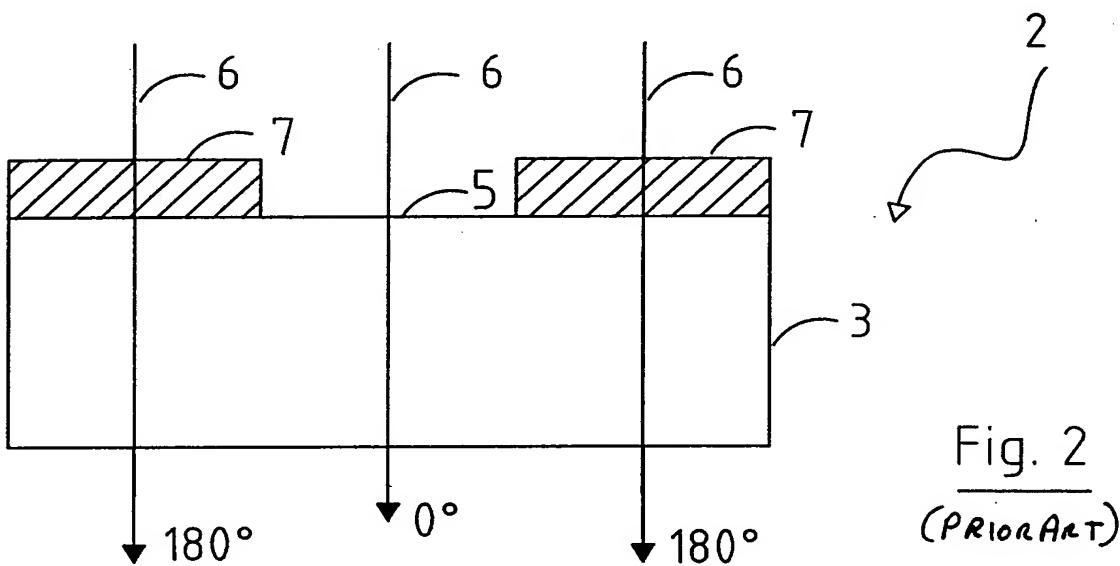
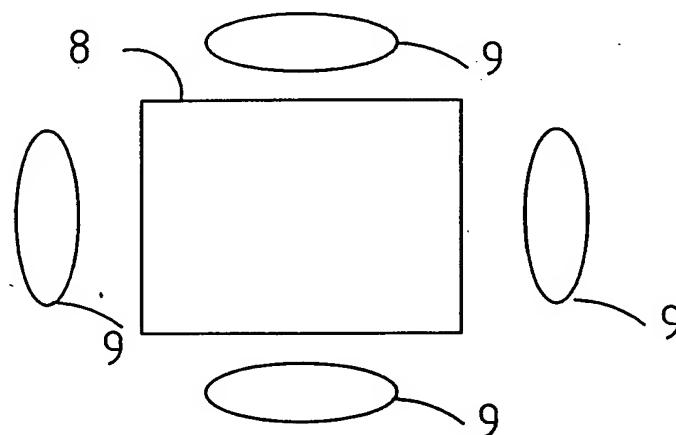
Docket No.: S1022.80434US01

please charge any deficiency to Deposit Account No. 23/2825. In view of the above amendment,  
applicant believes the pending application is in condition for allowance.

Dated: January 26, 2006

Respectfully submitted,

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Fig. 1  
(Prior Art)Fig. 2  
(Prior Art)Fig. 3  
(Prior Art)

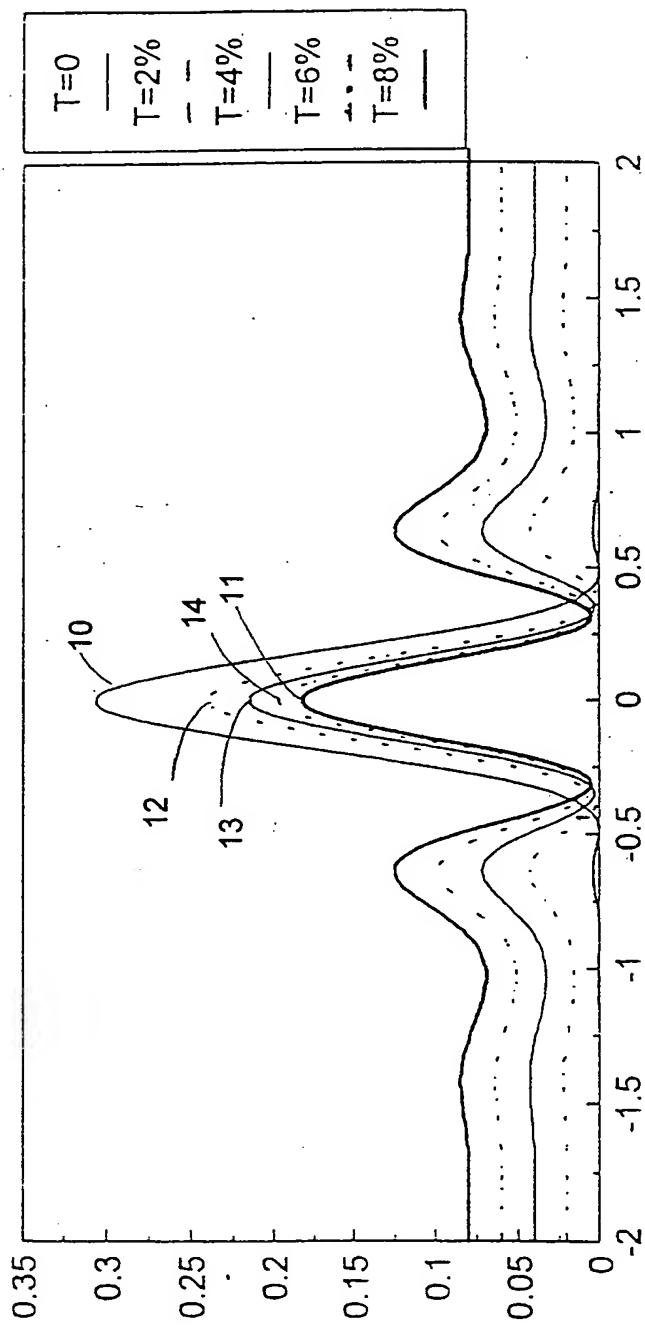
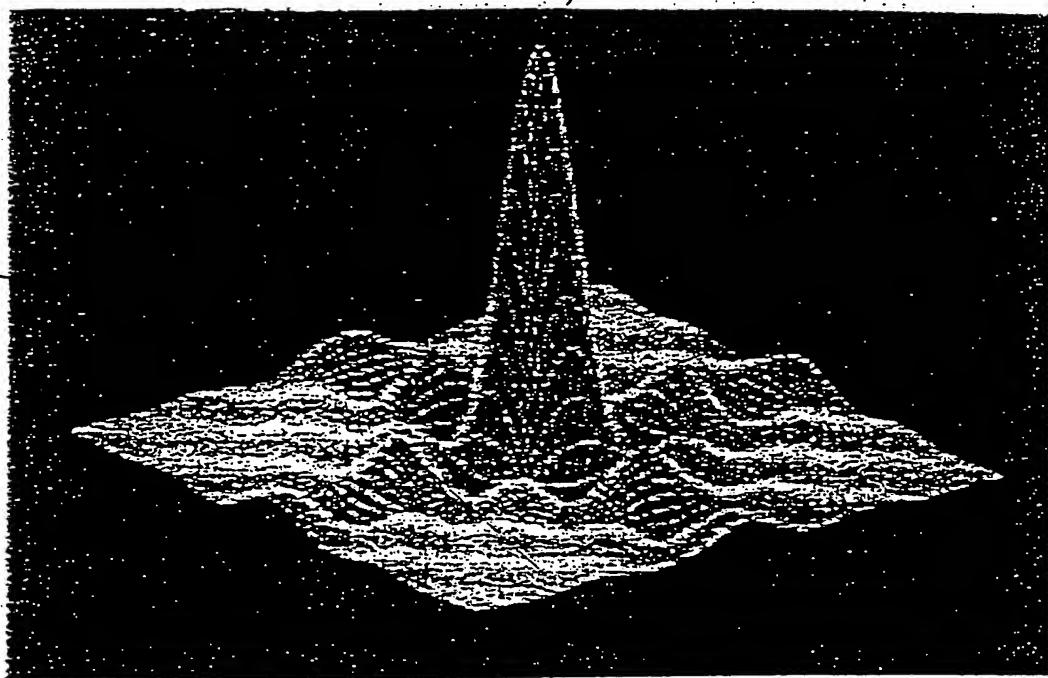


Fig. 4  
(Preior Art)

Serial No. 10/693,479

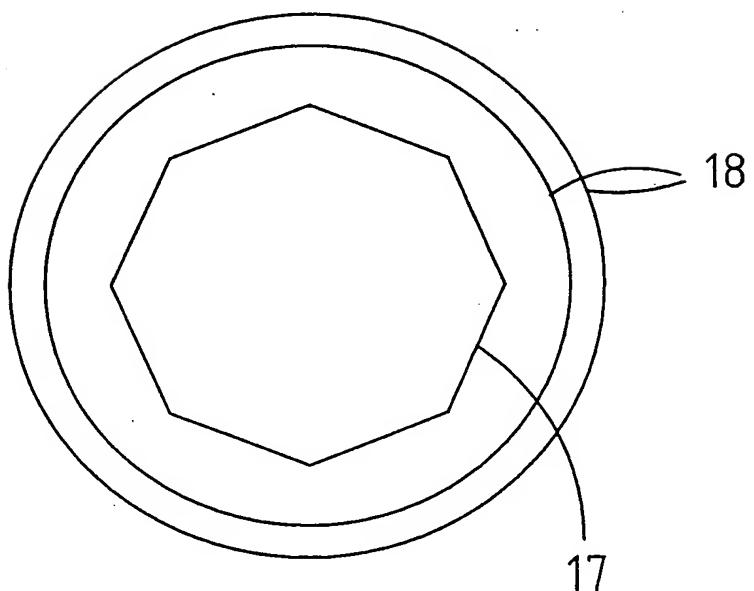
Lithographic mask for semiconductor devices with a polygonal-section etch window, in particular having a section of at least six sides  
Carmelo Romeo, Paolo Canestrari And Antonio Fiorino

ANNOTATED SHEET



16

Fig. 5  
(PRIOR ART)



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Fig. 8